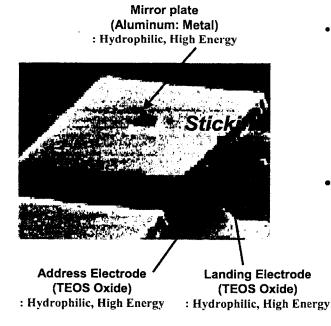
Nanotribological Characterization of Fluorocarbon Thin Film by Plasma Enhanced CVD

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2001. 7. 13

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Background



- Interaction Force
 - Capillary Force (in Humidity)
 - Electrostatic Force
 - van der Waals Force
- Due to Sticking
 - Out of order
 - Problems of Yield & Reliability

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Motivation

Depositing Fluorocarbon Thin Films from Plasma Enhanced CVD Method

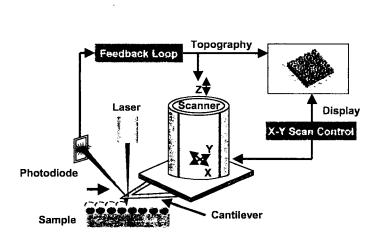
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Change Hydrophilic into Hydrophobic Surface

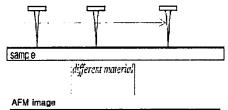
Establish Optimized Fabrication Process

Characterization of Friction Force of Fluorocarbon Thin Films by LFM

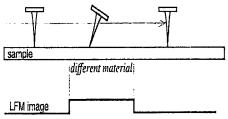
Introduction of AFM/LFM



Schematic Diagram of AFM/LFM



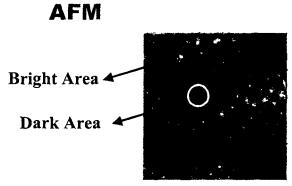
No deflection of cantilever for AFM



Lateral deflection of the cantilever from changes in surface friction

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AFM | LFM Measurement



Bright Area : High Height

• Dark Area : Low Height

Bright Area Dark Area

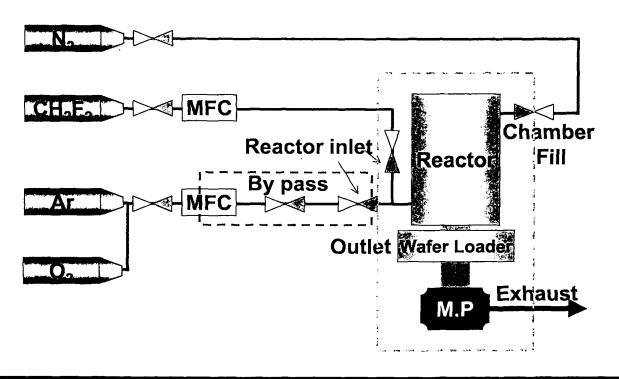
• Bright Area : High Friction

• Dark Area : Low Friction

LFM(Lateral Force Microscopy)

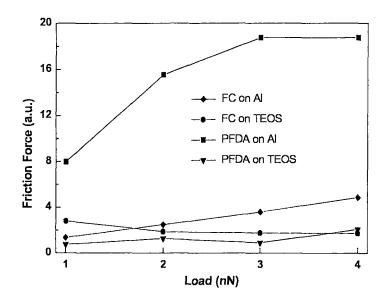
- · Useful for imaging variations in surface friction.
- Lateral force can be changed by chemical composition, viscosity and adhesion of materials.
- Friction force is not absolute value. It's relative value.

Experimental Setup



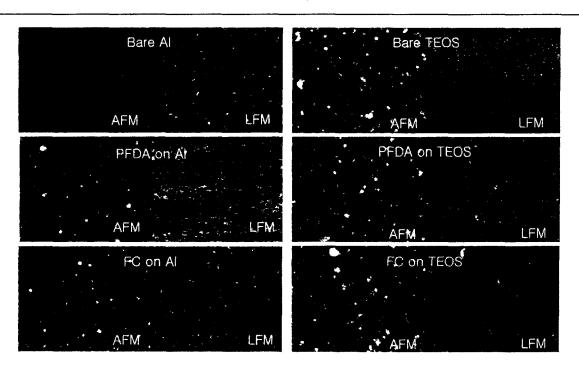
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Friction Force Signal by LFM



Friction force signal on the perfluoropolymer films as a function of the externally normal force obtained by LFM

AFM | LFM Images (5μ m imes 5μ m) before and after Film Deposition on AI & TEOS



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Conclusion

- AFM/LFM showed a more homogeneous coverage of films on TEOS than on AI
- The high friction characteristic of PFDA film on AI might be attributed to the poor coverage of the film on the surface.

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